Basic Self-Aligned Double Poly Bipolar Process
Initial Steps: Buried Subcollector Formation, n-epi growth, LOCOS process, p+ poly deposition, oxide growth.
P+ poly lithography, using oxide as a hard mask to open up window for intrinsic base formation.
Extrinsic Base Diffusion in oxygen environment (oxidation occurs as well)
More oxide deposition to the desired thickness (spacer width) to ensure good intrinsic/extrinsic link (but not too close either) RIE etch to form oxide spacer
Intrinsic Base Implant

Diagram showing layers: Oxide, P+ Poly, STI, P+, n-epi, B+
HF dip to break thin oxide at surface for poly emitter deposition
N+ poly deposition
Emitter drive in, base doping activation